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Supporting information

Fluorinated Silsesquioxane-based Photoresist as ideal Material with High-Performance for Ultraviolet Nanoimprinting

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Table S1. Surface free energy parameters of test liquids

Liquid	γ_L	γ^{LW}	γ^+	γ^-
Diiodomethane	50.8	50.8	0	0
Ethylene glycol	48.0	29.0	3.0	30.1
Water	72.8	21.8	25.5	25.5

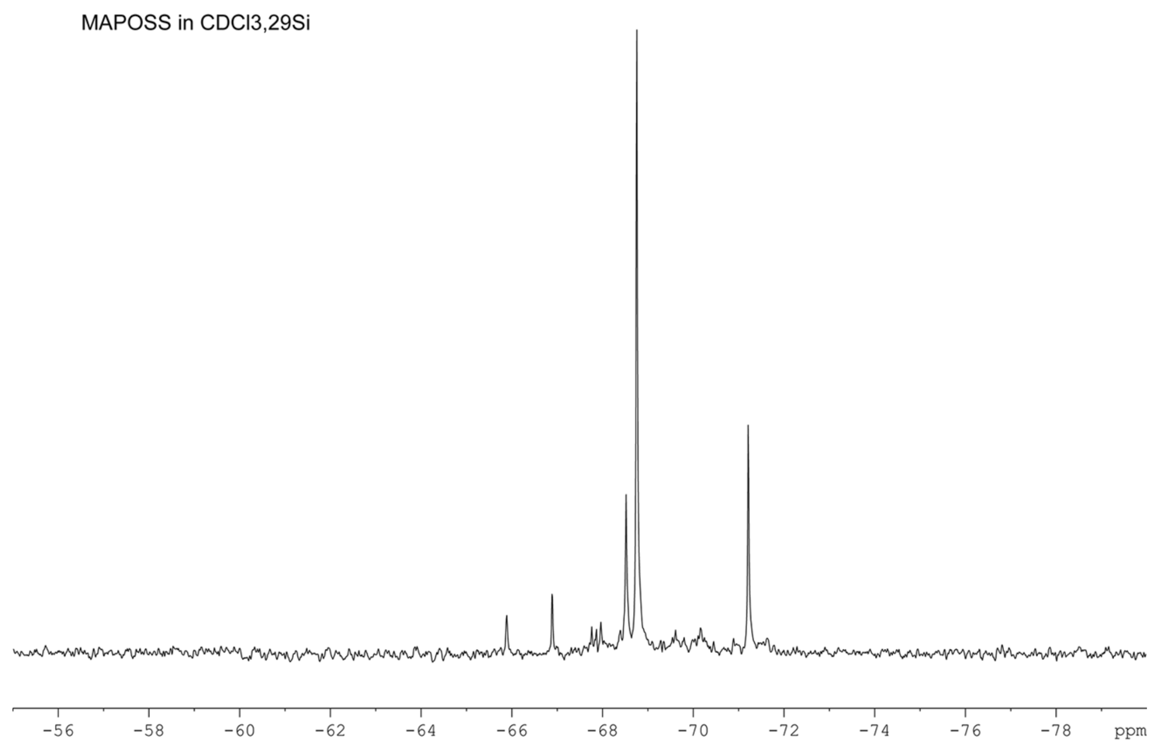

Fig. S1 ^{29}Si NMR spectrum of MAPOSS in $CDCl_3$

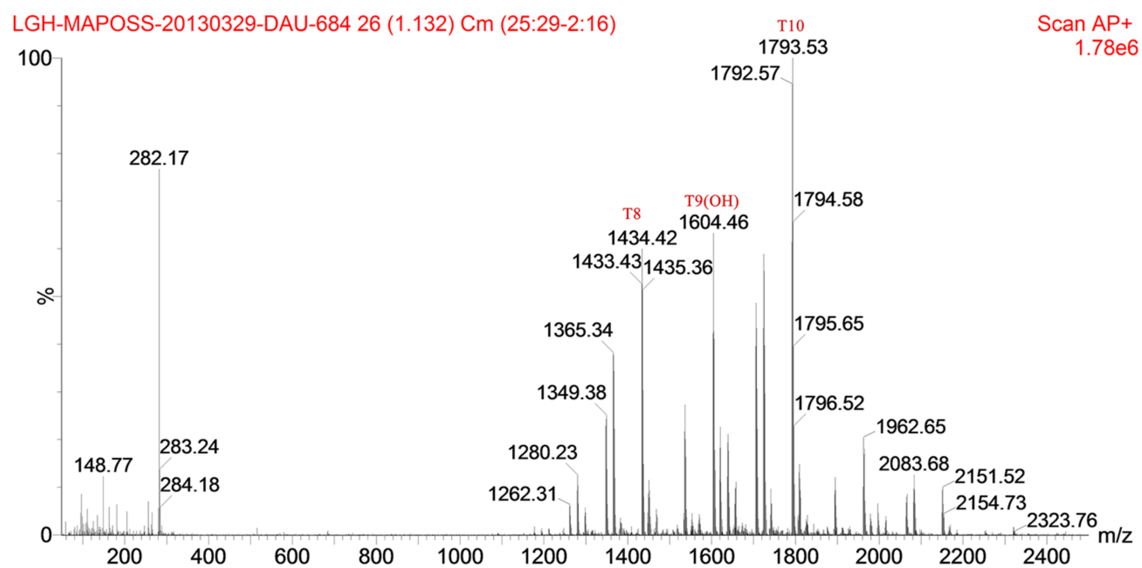

Fig. S2 Mass distribution of the MAPOSS from LC-MS

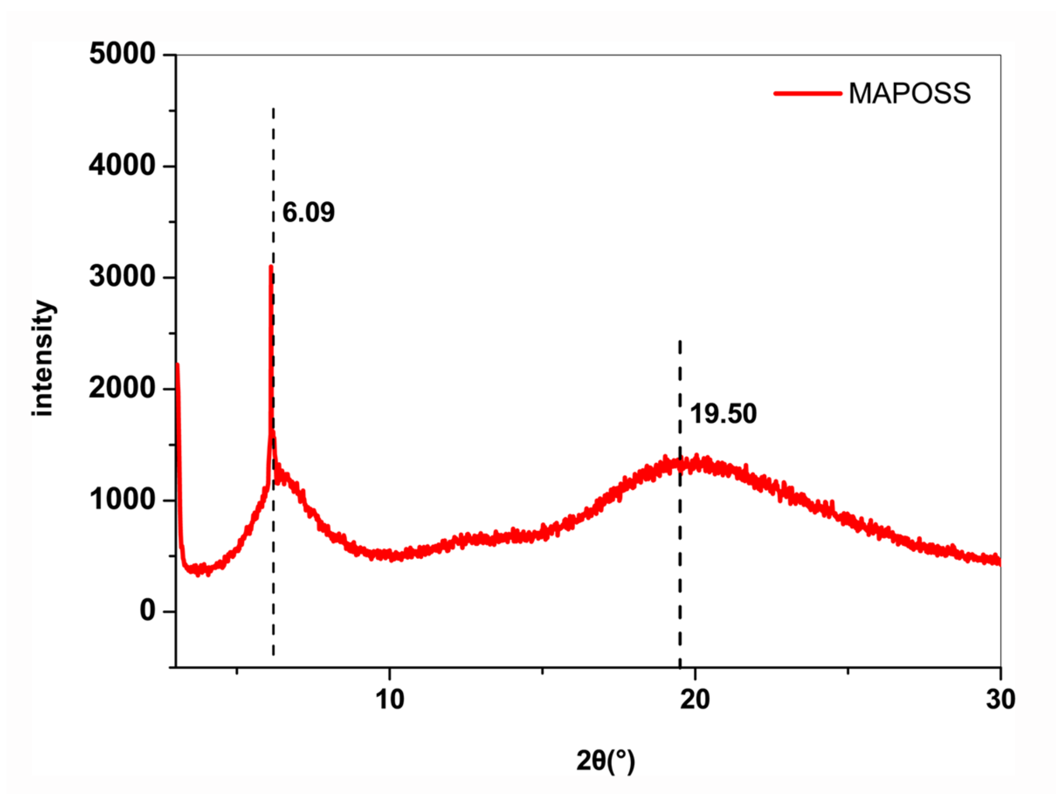

Fig. S3 XRD of the MAPOSS